



Electromigration on Signal Interconnects

(20140089, Dr. Sachin Sapatnekar)

Technology ID

20140089

Category

Engineering & Physical
Sciences/Nanotechnology
Engineering & Physical
Sciences/Semiconductor
Software & IT/Algorithms
Software & IT/Simulation &
Modeling

Efficiently Characterizes Cell-internal Electromigration

The problem of cell-internal electromigration (EM) on signal interconnects within a standard cell is solved using this technology which efficiently characterizes EM characteristics of gates in a standard cell library, under all pin positions, based on a single circuit simulation and graph-based methods. The approach uses Joule heating effects to model and efficiently characterize cell-internal EM to analyze the lifetime of large benchmark circuits. A related method optimizes circuit lifetime by changing pin positions in gates within a circuit. This procedure has demonstrated an approximate 60% increase in circuit lifetime.

Optimization of Circuit Lifetime

Standard cell-based gate libraries are the bedrock of integrated circuit design. Electromigration (EM) in on-chip metal interconnects is a critical reliability failure mechanism in nanometer-scale technologies and is an increasing problem in integrated circuits that reduces circuit lifetime. Traditionally, EM affected global wires, but in current and future technologies, within-gate wires will also be significantly affected. Currently, EM checks in existing technologies are performed ad hoc; no current methods systematically perform cell-internal EM or allocate pin positions to increase the lifetime of a circuit that uses numerous standard cells. This technology provides a systematic and computationally efficient way for analyzing cell-level EM and translating it to an analysis and optimization of circuit level lifetimes.

BENEFITS AND FEATURES:

- Models and efficiently characterizes cell-internal EM
- Characterizes EM characteristics of gates in a standard cell library under all pin positions
- Analyzes lifetime of large benchmark circuits
- Optimizes circuit lifetime
- Joule heating effects
- Solves cell-internal EM problems
- Approximate 60% increase in circuit lifetime

APPLICATIONS:

- Integrated circuit design
- Circuit design

Phase of Development - Prototype dev

Researchers

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Publications

[*A Systematic Approach for Analyzing and Optimizing Cell-Internal Signal Electromigration*](#)

IEEE/ACM International Conference on Computer-Aided Design, Digest of Technical Papers, ICCAD. 2015, pp. 486 – 491, 2014

[*Cell-Internal Electromigration: Analysis and Pin Placement Based Optimization*](#)

IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems, Vol. 35, No. 2, pp. 220 – 231, February 2016

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